

Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application:

1 1. (currently amended) A device for holding a nanolithography template used for
2 imprinting a nanolithography pattern on a substrate, said device comprising:

3 a body having an opening to receive said nanolithography template, said body for
4 positioning said template relative to said substrate for imprinting said nanolithography pattern on
5 said substrate; and

6 a supporting plate coupled to said body and positioned relative to said nanolithography
7 template to support a force of said imprinting on said nanolithography template, with said
8 supporting plate being substantially transparent to a curing agent.

1 2. (original) The device as recited in claim 1 wherein said curing agent comprises
2 ultraviolet radiation.

1 3. (original) The device as recited in claim 1 wherein said supporting plate is formed
2 from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

1 4. (currently amended) The device as recited in claim 1 further including a vacuum
2 system in fluid communication with said supporting plate to apply a vacuum to said
3 nanolithography template.

1 5. (original) The device as recited in claim 1 further including a vacuum system in
2 fluid communication with said supporting plate to apply a vacuum between said supporting plate
3 and said body.

1 6. (currently amended) The device as recited in claim 1 wherein said supporting
2 plate is configured to reduce deformation of said nanolithography template due to forces present
3 during an imprint lithography process.

1 7. (original) The device as recited in claim 1 further including a reflective element
2 connected to a portion of said body located within said opening.

1 8. (currently amended) A device for holding a nanolithography template used for
2 imprinting a nanolithography pattern on a substrate, said device comprising:

3 a body having an opening to receive said nanolithography template, said body for
4 positioning said template relative to said substrate for imprinting said nanolithography pattern
5 on said substrate; and

6 a supporting plate coupled to said body and positioned relative to said nanolithography
7 template to support a force of said imprinting on said nanolithography template, with said
8 supporting plate substantially transparent to ultraviolet radiation.

1 9. (original) The device as recited in claim 8 wherein said supporting plate is formed
2 from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

1 10. (currently amended) The device as recited in claim [[181]] 8 further including a
2 vacuum system in fluid communication with said supporting plate to apply a vacuum to said
3 nanolithography template.

1 11. (original) The device as recited in claim 8 further including a vacuum system in
2 fluid communication with said supporting plate to apply a vacuum between said supporting plate
3 and said body.

1 12. (currently amended) The device as recited in claim 8 wherein said supporting
2 plate is configured to reduce deformation of said nanolithography template due to forces present
3 during an imprint lithography process.

1 13. (original) The device as recited in claim 8 further including a reflective element
2 connected to a portion of said body located within said opening.

1 14. (currently amended) A device for holding a nanolithography template used for
2 imprinting a nanolithography pattern on a substrate, said device comprising:

3 a body having an opening to receive said nanolithography template, said body for
4 positioning said template relative to said substrate for imprinting said nanolithography pattern on
5 said substrate;

6 a supporting plate coupled to said body and positioned relative to said nanolithography
7 template to support a force of said imprinting on said nanolithography template, with said
8 supporting plate substantially transparent to a curing agent; and

9 a vacuum system in fluid communication with said supporting plate to apply a vacuum
10 between said supporting plate and said body.

1 15. (original) The device as recited in claim 14 wherein said curing agent comprises
2 ultraviolet radiation.

1 16. (original) The device as recited in claim 14 wherein said supporting plate is
2 formed from material selected from a set of materials consisting of quartz, sapphire, and silicon
3 dioxide.

1 17. (currently amended) The device as recited in claim 14 wherein said supporting
2 plate is configured to reduce deformation of said nanolithography template due to forces present
3 during an imprint lithography process.

1 18. (original) The device as recited in claim 14 further including a reflective element
2 connected to a portion of said body located within said opening.